

Notice of References Cited

Application/Control No.

09/893,340

Applicant(s)/Patent Under

Reexamination

KANG ET AL.

Examiner

Erik Kielin

Art Unit

2813

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	B	US-5,141,878	08-1992	Benton et al.	257/461
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	W	Merriam Webster's Collegiate Dictionary, 10th ed., p. 388.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.